

FORM PTO-1449 (Modified)
U.S. Department of Commerce, Patent and Trademark Office

Docket No.

01-234

Serial No.

Applicants

Colin D. Yates et al.

Filing Date
HerewithGroup
UnknownJ1011 U.S. PTO
10/006398

11/30/01

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)

U.S. Patent Documents

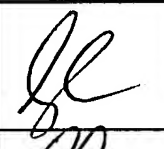


*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
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Foreign Patent Documents

Translation

		Document Number	Date	Country	Class	Subclass	Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AR	Bischoff, Joerg, et al., "Light-Diffraction-Based Overlay Measurement", (Presented at the Metrology, Inspection, and Process Control for Microlithography XV at Santa Clara, CA, February 26 - March 1, 2001), <u>Proceedings of SPIE</u> , Vol. 4344, 2001, pp. 222-233 (Abstract only).
	AS	Hatab, Ziad R., et al., "Optical Diffraction Tomography for Latent Image Metrology", (Presented at the Metrology, Inspection, and Process Control for Microlithography XI), <u>Proceedings of SPIE</u> , Vol. 3050, 1997, pp. 271-280 (Abstract only).
	AT	McNeil, John R., "Scatterometry Applied to Microelectronics Processing", <u>LEOS Newsletter</u> , Vol. 14, No. 5, October, 2000, pp. 26-27.

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	BI						
	BJ						
	BK						

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	BL							
	BM							
	BN							
	BO							
	BP							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	BR	Raymond, Christopher J., et al., "Asymmetric Line Profile Measurement Using Angular Scatterometry", (Presented at the Metrology, Inspection, and Process Control for Microlithography XV at Santa Clara, CA, February 26 - March 1, 2001), <u>Proceedings of SPIE</u> , Vol. 4344, 2001, pp. 436-446.
	BS	
	BT	

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